

New Insights Towards High-Temperature Ethanol-Sensing Mechanism of ZnO-Based Chemiresistors

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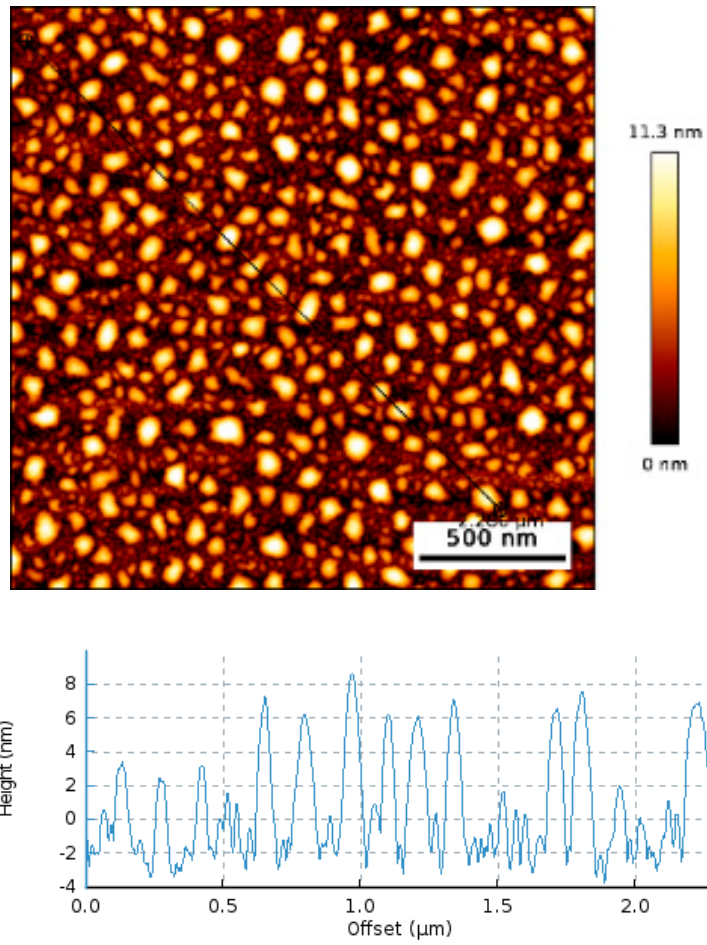


Figure S1. AFM image of the ZnO seed layer deposited on silicon wafer by PLD

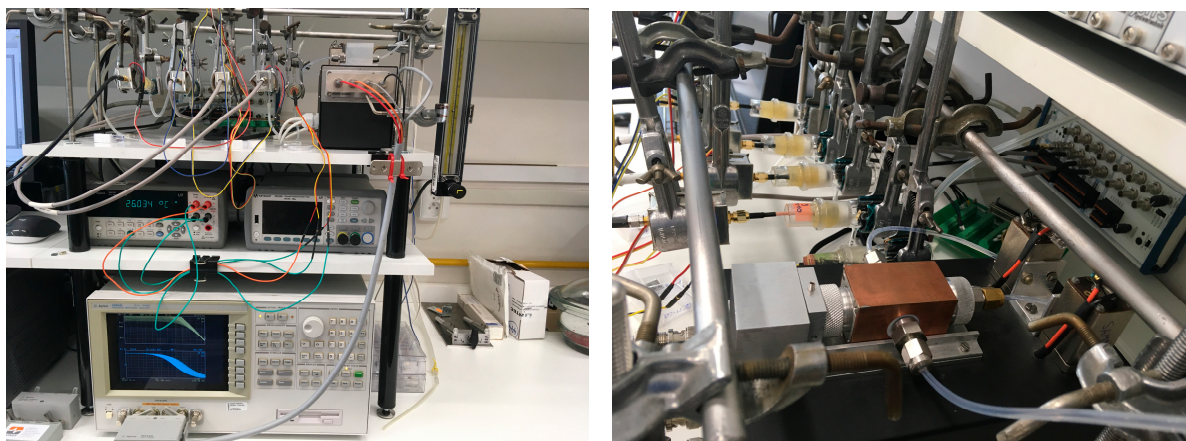


Figure S2. Photo of measurement apparatus used for the sensor response measurements in AC mode

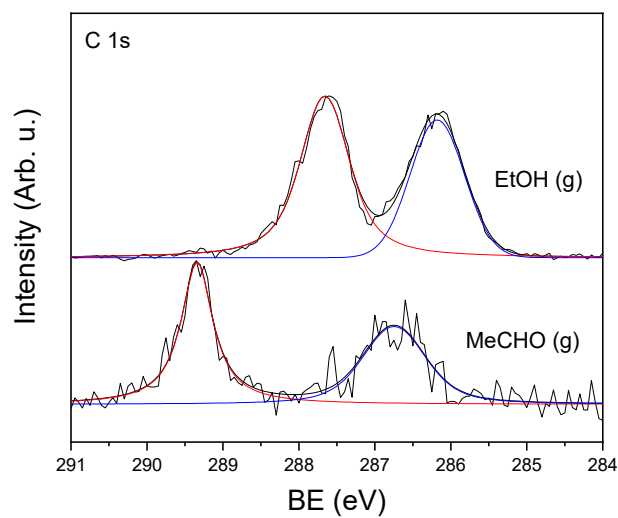


Figure S3. Reference gas-phase C 1s NAP-XPS spectra acquired from the O₂/EtOH and O₂/MeCHO gas mixtures.

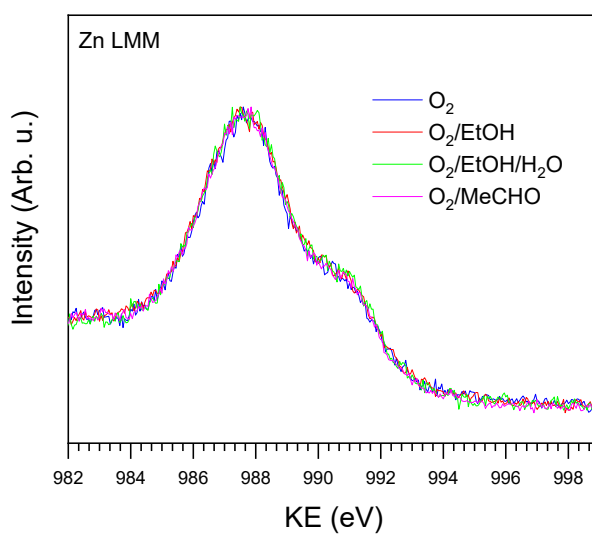


Figure S4. NAP-XPS spectra of the Zn LMM acquired from the ZnO NRs based sensor in the presence of O₂, O₂/EtOH, O₂/EtOH/H₂O and O₂/MeCHO at 327 °C.